

Study of GaN Metal - Semiconductor - Metal Photodetectors

吳振緯、蕭宏彬

E-mail: 9708112@mail.dyu.edu.tw

ABSTRACT

In this thesis, Ni/Au Schottky contacts on n-GaN were fabricated and characterized. The barrier height and ideality factor were extracted from the I-V and C-V measurements. In order to enhance the barrier height and evaluate the thermal stability, the Schottky diodes were treated with various annealing temperatures and annealing times. The thermal annealing processes were conducted under nitrogen ambient in a furnace tube. The temperatures and times used for thermal annealing were from 300 to 550 and from 5min to 60min, respectively. From the results, we found that thermal annealing at 300 and 400 can be used to increase about 0.19eV (I-V) and 0.17eV (C-V) of barrier height. However, thermal annealing at 500 and 550 for a periodic of time will make barrier height degrade. Based on X-ray diffraction studies, the re-crystallization of metal film and the formation of Ni gallide phase could be the reasons for the improvement of barrier height of Ni/Au Schottky contact on n-GaN at 300 ~ 400 annealing temperature. The degradation of the Schottky barrier heights for the contacts annealed above 500 was mostly due to interface phase changes. By the way, GaN MSM photodetectors with Ni/Au contacts annealed at 400 showed a reduction in the leakage current by three orders of magnitude than the as deposited sample.

Keywords : GaN ; Schottky contact ; Ni/Au ; Schottky barrier height

Table of Contents

封面內頁 簽名頁 授權書	iii 中文摘要
iv 英文摘要	v 誌謝
vi 目錄	vii 圖目錄
ix 表目錄	x 第一
章 前言	1 1.1 研究動機背景與目的
1 第二章 Labview 及GPIB	3 2.1 Labview 簡介
3 2.2 IEEE-488簡介	5 第三章 理論
10 3.1 金屬 - 半導體接面原理	10 3.2 金屬 - 半導體 - 金屬光檢測器原理
17 第四章 元件製作與量測	21 4.1 試片準備步驟
21 4.2 蕭特基二極體之製作流程	23 4.3 金屬 - 半導體 - 金屬光檢測器之製作流程
24 4.4 蕭特基二極體特性量測	27 4.5 金屬 - 半導體 - 金屬光檢測器電流 - 電壓特性
31 第五章 結果與討論	32 5.1 蕭特基二極體量測分析
32 5.2 XRD量測分析	40 5.3 金屬-半導體-金屬光檢測器暗電流特性分析
42 5.4 金屬-半導體-金屬光檢測器光電流特性分析	44 第六章 結論
48 參考文獻	49

REFERENCES

- 【1】 M.A Khan, M.S Shur, J.N. Kuznia, Q. Chen, J. Burm, W. Schaff, Appl. Phys. Lett. 66 (1995) 1083. 【2】 O. Aktas, Z.F. Fan, S.N. Mmohammad, A.E. Botchkarev, H. Morkoc, Appl. Phys. Lett. 69 (1996) 3872. 【3】 T. Mukai, D. Morita, and S. Nakamura, " High-power UV InGaN/AlGaN double-heterostructure LEDs, " J. Crystal. Growth, Vol.189/190, pp.778, 1998. 【4】 G.S. Nakamura, " InGaN-based violet laser diodes, " Semicond. Sci. Technol. Vol.14, pp.27, 1999. 【5】 M.A. Khan, J. N. Kuznia, D. T. Olson, M. Blasingame, and A.R. Bhattarai, " Schottky barrier photodetector based on Mg-doped p-type GaN film, " Appl. Phys. Lett. , Vol.63, pp.2455, 1993. 【6】 E. Monroy, F. Calle, E. Munoz, and F. Omnes, " Effects of Bias on the Responsivity of GaN Metal-Semiconductor-Metal Photodiodes " , Phys. Stat. Sol. (a), Vol.176, pp.157, 1999. 【7】 M. A. Khan, J. N. Kuznia, A. R. Bhattarai, and D. T. Olson, " Metal semiconductor field effect transistor based on single crystal GaN, " Appl. Phys. Lett. , Vol.62, pp.1786, 1993. 【8】 D.Mistele, Mater. Sci. Eng. B93 (2002) 107. 【9】 M.A. Khan, J. N. kuznia, D. T. Olson, W. J. Schaff, J. W. Burm, and M. S. Shur, " Microwave performance of a 0.25 μ m gate AlGaN/GaN heterostructure field effect transistor, " Appl. Phys. Lett. , Vol.65, pp.1121, 1994. 【10】 F. Ren, C. R. Abernathy, J. M. Van Hove, P. P. Chow, R. Hickman, J. J. Klaasen, R. F. Kopf, H. Cho, K. B. Jung, J. R. LaRoche, R. G. Wilson, J. Han, R.J. Shul, A. G. Baca, and S. J. Pearton, " 300 GaN/AlGaN

Heterojunction Bipolar Transistor, " MRS. Internet J. Nitride Semicond. Res. , Vol.3, pp.41, 1998. 【11】J. Moon, M. Micovic, A. Kurdoglian, P. Janke, P. Hasmimoto, W. Wong, L. McRay, C. Nguyen, IEEE Electron. Dev. Lett. 23(2002) 637. 【12】S. Pearson, Mater. Sci. Eng B82 (2001) 227. 【13】A. C. Schmitz, A. T. Ping, M. Asif Khan, Q. Chen, J. W. Yang and I. Adesida, " Mental contacts to n-type GaN, " J. Electron. Mater. , Vol.27, pp.255-260, 1997. 【14】E. V. Kalinina, N. I. Kuznetsov, V. A. Dmiteiev, K. G. Irvine and C. H. Carter, " Schottky barriers on n-GaN grown on SiC, " J. Elctron. Mater. , Vol.25, pp.831-834, 1995. 【15】S. N. Mohammad, Z. FaN, A. E. Botchkarev, W. Kim, O. Aktas, A. Salvadorand H. Morkoc, " Near-ideal platinum-GaN Schottky diodes, " Electron. Lett. , Vol.32, pp598-599, 1996. 【16】柯仕鴻,林易賢,趙儒民,龔俊豪、莊金章,PAC 於客製化遊艇監控系統之應用,第六屆NI徵文比賽. 【17】翁弘亦,黃晨軒,李志軒,心血管疾病快速檢測與心電信號自動監測之設計,第六屆NI徵文比賽. 【18】自動化量測系統用於遠端教學網頁平台:廖瑋星,楊嘉仁,王鴻諭,涂政良,王順忠,第六屆NI徵文比賽. 【19】楊凱智,黃鴻文,陳彥百,吳啟耀,馬達及驅動器之特性測試系統,第六屆NI徵文比賽. 【20】楊奇達,鄭碩仁,LabVIEW應用於光電半導體材料自動化量測技術,第六屆NI徵文比賽. 【21】殷尚彬,湯鈞汶,黃秉鈞LED 多物理特性動態量測系統開發第六屆NI徵文比賽. 【22】黃正雄,王太伸,林光儀,LabVIEW 於光電半導體材料研究技術之應用-螢光光譜 (PL) 第四屆NI徵文比賽. 【23】E. H. RHODERICK, R. H. WILLIAMS, Metal - Semiconductor Contacts, 2nd, p. 18 and p. 51. 【24】A. C. Schmitz, A. T. Ping, M. Asif Khan, Q Chen, J. W. Yang " Schottky barrier properties of various metals on n-type GaN, " Semicond Sci Technol Vol. 11, pp 1464-1467, 1996 【25】N. Miura, T. Nanjo, M. Suita, T. Oishi, Y.Abe, " Thermal annealing effects on Ni/Au based Schottky contacts on n-GaN and AlGaN/GaN with insertion of high work function metal, " Solid-State Electronics Vol 48, pp689-695, 2004. 【26】V. Rajagopal Reddy, P. Koteswara Rao, " Annealing temperature effect on electrical and structural properties of Cu/Au Schottky contact to n-type GaN, " Microelectronic Science and Engineering, Vol.85, Issue.2, pp.470-476, 2007. 【27】V. Rajagopal Reddy, P. Koteswara Rao, " Annealing effects on structural and electrical properties of Ru/Au on n-GaN Schottky contacts, " Materials Science and Engineering B, Vol.137, Issues.1-3, pp.200-204, 2007. 【28】Y. K. Su, S. J. Chang, C. H. Chen, J. F. Chen, G. C. Chi, J. K. Sheu,W. C. Lai, J. M. Tsai, " GaN Metal-Semiconductor-Metal Ultraviolet Sensors With Various Contact Electrodes, " IEEE Sensors Journal, Vol.2,NO.4, 2002.